

**AMENDMENTS TO THE CLAIMS:**

This listing of claims will replace all prior versions and listings of claims in the application:

1-10. (Canceled)

11. (Withdrawn) A liquid film forming method of dropping a liquid from a dropping nozzle or dropping nozzles of a dropping unit onto a substrate, and providing relative movement between the dropping unit and the substrate to change a dropping point of the substrate while keeping the liquid dropping on the substrate, so as to form a liquid film on the substrate,

wherein a change amount of a contact angle of the liquid to the substrate is within  $\pm 2$  degrees during a time from 5 seconds to 60 seconds after the dropping of the liquid when a minute amount of the liquid is dropped onto a minute area of the substrate.

12. (Withdrawn) The liquid film forming method according to claim 11, wherein control of the change amount of the contact angle of the liquid dropped onto the substrate to the substrate within  $\pm 2$  degrees is attained by adjusting the ratio of a surfactant to a solvent and an application agent constituting the liquid.

13. (Withdrawn) A liquid for application used in a liquid film forming method of dropping the liquid adjusted to be spread into a give amount on a substrate to be processed from a dropping nozzle or dropping nozzles of a dropping unit onto the substrate, and then moving the dropping unit and the substrate relatively while keeping the liquid dropping on the substrate, so as to form a liquid film on the substrate, comprising a solvent, an application agent, and a surfactant,

wherein the ratio of the surfactant to the solvent and the application agent is adjusted in such a manner that when a minute amount of the liquid is dropped onto a minute area of the substrate, a change amount of a contact angle of the liquid to the substrate is within  $\pm 2$  degrees during a time from 5 seconds to 60 seconds after the dropping of the liquid.

14. (Cancelled)

15. (Currently Amended) A liquid film forming method of dropping a liquid to be spread on a substrate to be processed from a dropping nozzle or dropping nozzles of a dropping unit onto the substrate, and then moving the dropping unit and the substrate relatively while keeping the liquid dropping on the substrate, so as to form a liquid film on the substrate,

wherein the relative movement of the dropping unit and the substrate is composed of straight movement along a file direction in which the dropping unit passes

from one end side of the substrate through an upper space over the substrate to the other end side of the substrate, and movement along a rank direction, and

a distance between a dropping start position on the substrate and the adjacent ~~an~~ edge of the substrate closest to the dropping start position is relatively larger than a distance between a dropping end position on the substrate and the adjacent ~~an~~ edge of the substrate closest to the dropping end position ~~along the rank direction~~, and ~~[[the]]~~ a distance between an end of the ~~[[a]]~~ liquid film and the adjacent ~~an~~ edge of the substrate closest to the end of the liquid film ~~along the file direction~~ is set so as to gradually ~~become smaller~~ decreases from the dropping start position to the dropping end position.

16. (Currently Amended) The liquid film forming method according to claim 15, wherein the distance between the end of the liquid film and the adjacent ~~edge~~ of the substrate closest to the end of the liquid film is decided ~~dependently~~ based on ~~[[such]]~~ a distance that the liquid flows on the substrate after the dropping of the liquid on the substrate.

17. (Currently Amended) The liquid film forming method according to claim 15, wherein the distance between the end of the liquid film and the adjacent ~~edge~~ of the substrate closest to the end of the liquid film is defined as a distance that the end of the liquid ~~[[film]]~~ flows on the substrate after the dropping of the liquid from the end of

the liquid film to reaches the end of the substrate closest to the end of the liquid film by-  
flow.

18. (Withdrawn) A liquid film forming method of dropping a liquid adjusted to be spread into a give amount on a substrate to be processed from a dropping nozzle or dropping nozzles of a dropping unit onto the substrate, and then moving the dropping unit and the substrate relatively while keeping the dropped liquid on the substrate, so as to form a liquid film on the substrate,

wherein the relative movement of the dropping unit and the substrate is composed of straight movement along a file direction in which the dropping unit passes from one end side of the substrate through an upper space of the substrate to the other end side of the substrate, and movement along a rank direction outside the substrate, or is composed of spiral movement in which the dropping unit goes from the substantial center of the substrate to the periphery thereof or from the periphery of the substrate to the substantial center thereof, and

the thickness of the liquid film is decided in the manner that the liquid film formed on the substrate flows to an extent which is substantially decided by gravitation applied to the liquid film.

19. (Withdrawn) The liquid film forming method according to claim 18, wherein the thickness of the liquid film is set to 20  $\mu\text{m}$  or less.

20. (Withdrawn) The liquid film forming method according to claim 11, wherein the relative movement of the dropping unit and the substrate is composed of straight movement along a file direction in which the dropping unit passes from one end side of the substrate through an upper space of the substrate to the other end side of the substrate, and movement along a rank direction perpendicular to the file direction outside the substrate.

21. (Withdrawn) The liquid film forming method according to claim 11, wherein the relative movement of the dropping unit and the substrate is composed of spiral movement in which the dropping unit goes from the substantial center of the substrate to the periphery thereof or from the periphery of the substrate to the substantial center thereof.

22. (Withdrawn) The liquid film forming method according to claim 11, wherein the dropping a liquid is performed by using a capillary phenomenon.

23. (Withdrawn) The liquid forming method according to claim 11, wherein the thickness of the liquid film is decided in the manner that the liquid film formed on the substrate flows to an extent which is substantially decided by gravitation applied to the liquid film.

24. (Withdrawn) The liquid film forming method according to claim 23,  
wherein the thickness of the liquid film is set to 20  $\mu\text{m}$  or less.